

# Laser-induced Damage Threshold (LIDT) in Optical Components



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# What is Laser-induced Damage ?

- Ü Laser-induced Damage (LID) is damage caused to an optical coating or substrate when irradiated by a Laser.
- Ü As early as 1962 McClung and Hellwarth ('Giant Optical Pulsation from Ruby') reported that 'output light burned holes in the silvered surfaces' of their ruby rod.
- Ü Since then, the power available from Laser has increased substantially and we are now regularly dealing with Petawatt lasers!

# The Basics

- Ü The Laser-induced Damage Threshold (LIDT) of optical materials is determined mainly by the following:
  - Ü Beam size (the more power is concentrated in one spot the more likely the damage)
  - Ü The Beam shape (Gauss / Supergauss – this will be examined in more detail later)
  - Ü The Beam quality (hot-spots)
  - Ü The coating / substrate materials (metals vs. dielectrics, coating and substrate quality)
  - Ü The environment (cleanroom vs. dusty environment)

# LID in common substrate materials

Commonly used optical substrate materials incur LID due to the following

Dielectric breakdown (Fused Silica, Diamond, Quartz, Sapphire)

Thermal absorption (LiNbO<sub>3</sub>, BK7)

Material	LIDT @ 1064nm in J/cm <sup>2</sup>
Fused Silica	$1.1 \times 10^7$
Sapphire (Al <sub>2</sub> O <sub>3</sub> )	$7 \times 10^6$
Diamond	$6 \times 10^7$
LiNbO <sub>3</sub>	$5 \times 10^4$
BK7	$4 \times 10^5$

# LID in optical coatings

- Ü Metal coatings predominantly damage as a result of thermal absorption
- Ü Dielectric coatings generally show much lower absorption than metal coatings and defect-induced damage is more common.
  - Ü Defects can be inclusions (dust particles)
  - Ü The substrate surface can encourage irregular growth of coating layers, leading to defects
  - Ü The coating parameters (deposition rate etc.) influence the quality of the coating.

# How to scale LIDT

Ü For any given LIDT ( $LIDT(t_1)$ ) at a pulse duration  $t_1$ , the approximate LIDT ( $LIDT(t_2)$ ) at pulse duration  $t_2$  is given by

$$LIDT(t_2) = LIDT(t_1) * (t_2/t_1)^{1/2}$$

Ü This rule works for pulse durations of approx. 1ns – 20ns.

# Coating designs for high LIDT requirements

- Ü In general, optical coatings made of ‘single stacks’, i.e. stacks of high- and low index coating materials of  $\lambda/4$  optical thickness, display the highest LIDT.
- Ü The choice of optical coating materials (and the deposition parameters) are important.

# What changes for Ultrafast Pulses?

- Ü Mero et al (Phys Rev B71, 115109) have undertaken fundamental work to estimate the LIDT (critical fluence) of a material as a function of the pulse duration and material band gap. For Formula see next slide.
- Ü Interestingly, they could not establish any relationship between LIDT and defects or impurities due to the manufacturing process. (confirmed by Stolz et al.)



# What changes for Ultrafast Pulses?

$$F_{th} = (C_1 + C_2 E_g) \tau_p^\kappa$$

$F_{th}$ : critical fluence

$E_g$ : material band gap

$\tau_p$ : pulse duration

$\kappa$ : material specific constant

$c_1$ : empirical factor,  $-0.16 \pm 0.02 \text{ J/cm}^2 \text{ fs}^{-\kappa}$

$c_2$ : empirical factor,  $0.074 \pm 0.004 \text{ J/cm}^2 \text{ fs}^{-\kappa} \text{ eV}^{-1}$

# Coatings for ultrafast applications

Material	$n_{800}$ (refractive index at 800nm)	$E_0$ (band gap energy)	$K$	Theoretical critical fluence in J/cm <sup>2</sup> for 15fs pulse
TiO <sub>2</sub>	2.39	3.3 eV	0.28+/-0.02	0.18
Ta <sub>2</sub> O <sub>5</sub>	2.17	3.8 eV	0.33+/-0.02	0.30
HfO <sub>2</sub>	2.09	5.1 eV	0.30+/-0.01	0.49
Al <sub>2</sub> O <sub>3</sub>	1.65	6.5 eV	0.27+/-0.01	0.67
SiO <sub>2</sub>	1.5	8.3 eV	0.33+/-0.01	1.11

Source: Mero et al, Phys. Rev. B71, 115109 (2005)

# What changes for Ultrafast Pulses?

- More recent work by Mangote et al (Optics Letters 37,9 1478, May 2012) looked into the relationship between the material's refractive index and its LIDT
- Unfortunately, data was compiled for a 500fs pulse at 1030nm
- The empirical law they found is:

$$\text{LIDT} = 12/n^2 \text{ J/cm}^2$$

# What changes for Ultrafast Pulses?

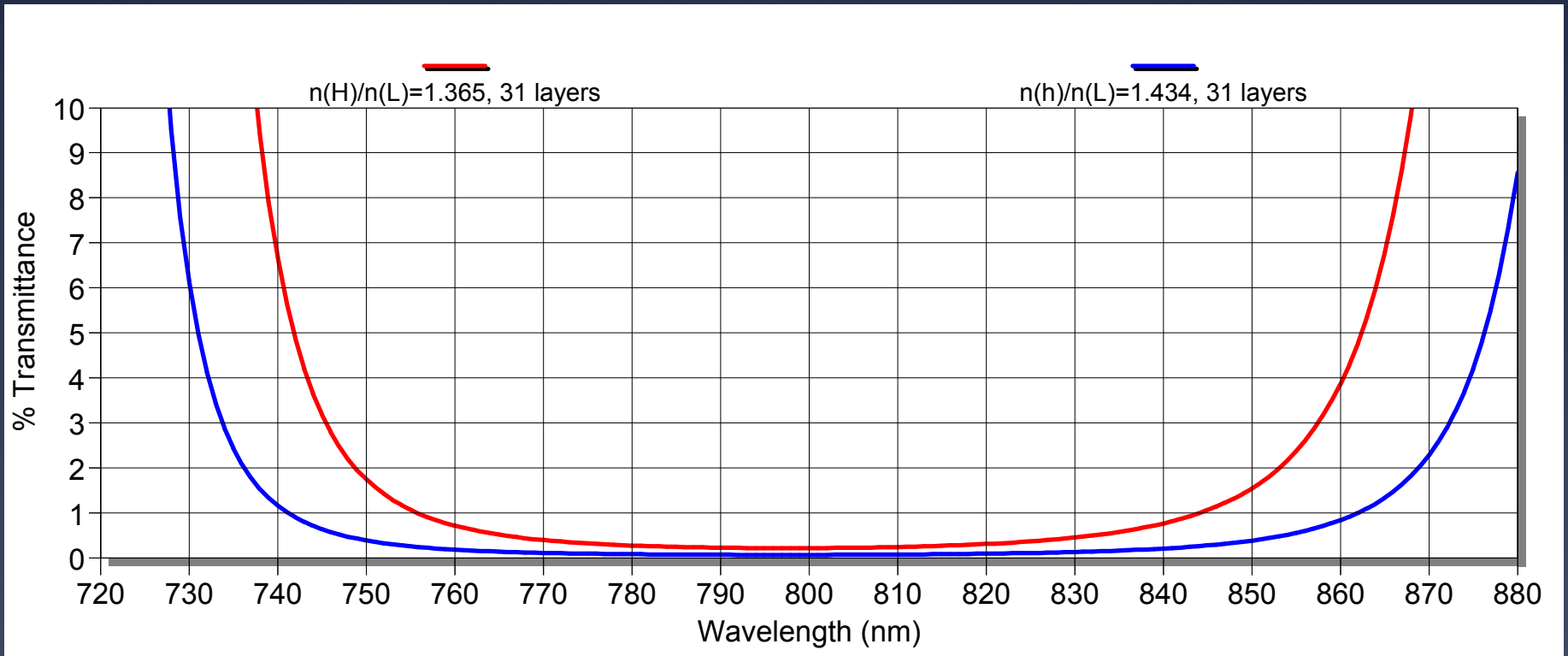
- While the authors are unable to give a scientific explanation for this equation it highlights a significant implication for coating design.
- The LIDT appears to decrease by a power of two with increasing refractive index !!!

# Coatings for ultrafast applications

- Ü ‘Single Stack’ coatings display a high LIDT and good Group Delay Dispersion (GDD).
- Ü Spectral breadth is limited by ratio of refractive index between the 2 coating materials.
- Ü ‘Natural’ limit on achievable breadth.

# Coatings for ultrafast applications

Performance shown under AOI of 45deg , p-POL



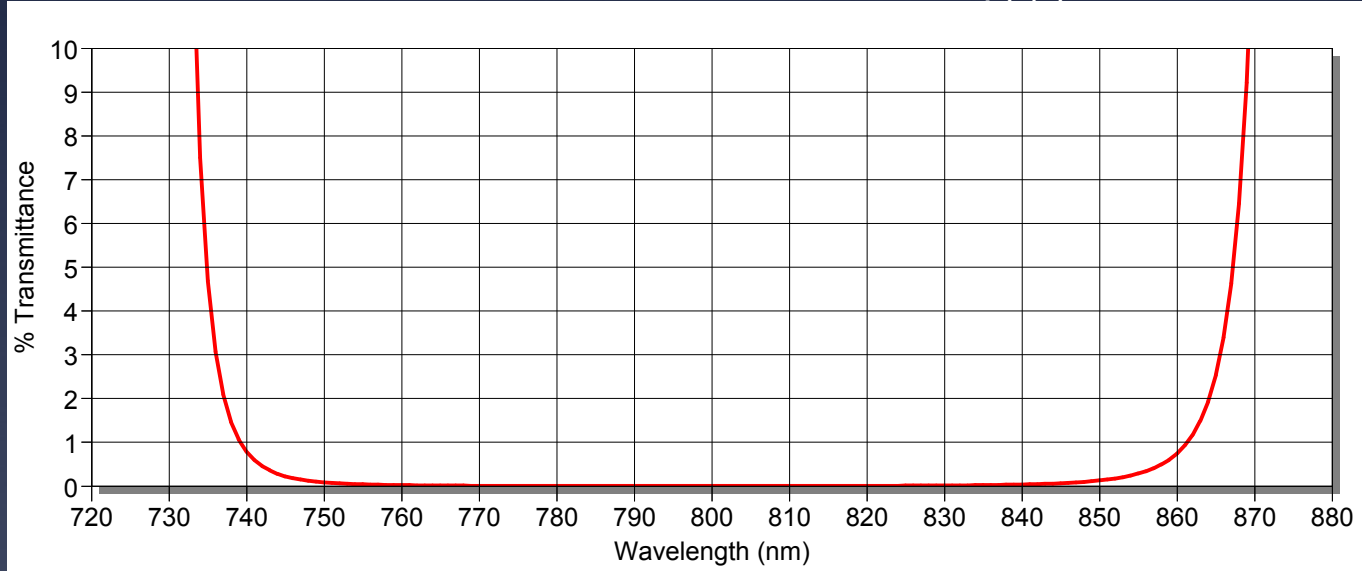
# Coatings for ultrafast applications

- Ü Stack 1 ( $n(H)/n(L)=1.365$ ) is compatible with high power
- Ü Stack 2 ( $n(H)/n(L)=1.434$ ) can only handle medium to low power
- Ü Bandwidth of at least 750-850nm is required by most customers
- Ü What can be done?

# Coatings for ultrafast applications

## Ü Solution 1: Combination of both stacks

Performance shown under AOI of 45deg , p-POL



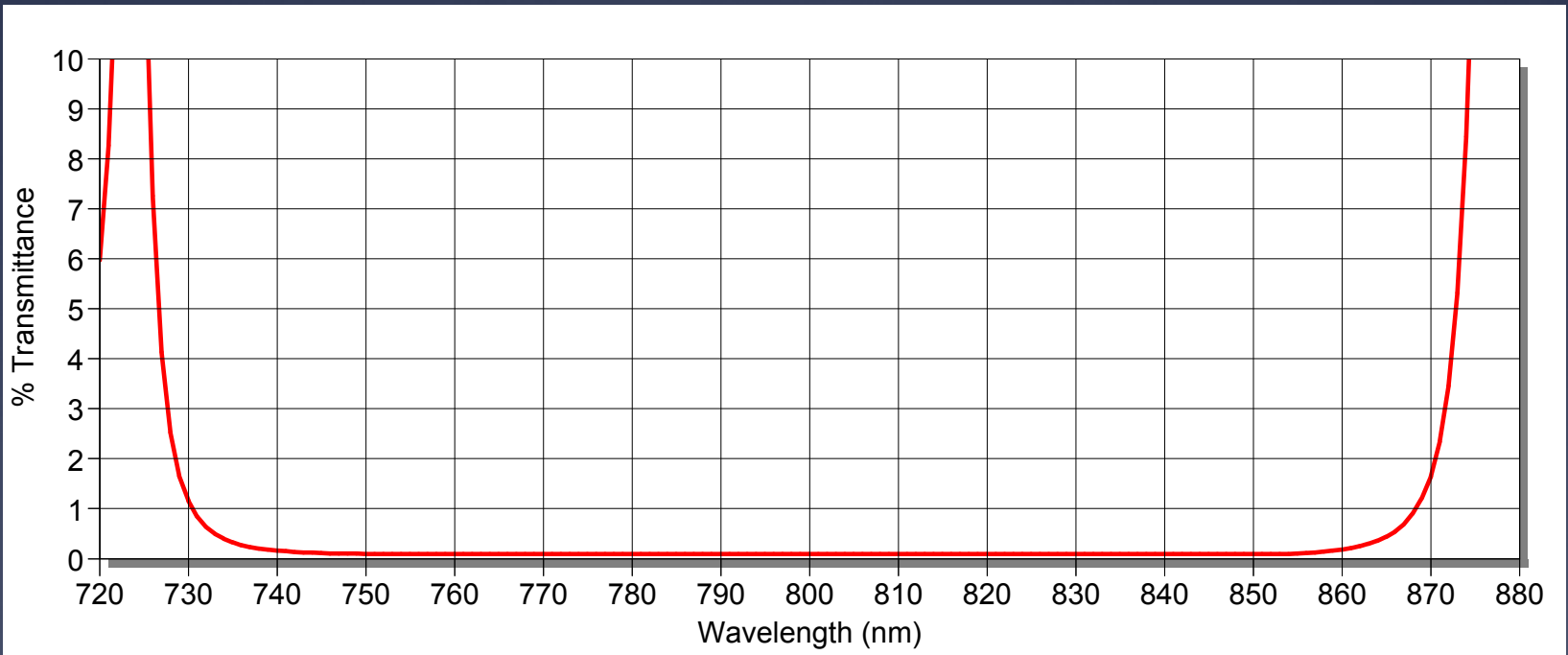
## Ü Good and easy solution, BUT:

- Ü Potentially problematic under vacuum (stress can cause crazing of the coating, especially for larger substrates)
- Ü Design can cause spikes in GDD
- Ü Cannot handle spectral Supergauss beamprofiles well (Low LIDT)



# Coatings for ultrafast applications

- Ü MPO's solution – optimised design
- Ü High LIDT, vacuum compatible (even for large substrates), low GDD, can be tailored to customer requirements.



Performance shown under AOI of 45deg , p-POL

# Any Questions ?

